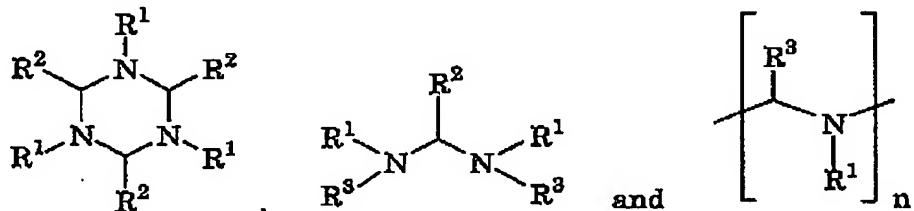


Docket No. 396.43366X00
 Serial No. 10/750,822
December 2, 2005

AMENDMENTS TO THE SPECIFICATION:

Please delete the paragraph on page 3, lines 6-19, and substitute therefor the following rewritten paragraph:

--The photoresist stripping agent of the present invention contains at least one formaldehyde-alkanolamine reaction product which is a product of the reaction between formaldehyde and an alkanolamine. As an example of the reaction product of an amine and an aldehyde, methylolamine has been known in the art. The photoresist stripping agent of the present invention contains, as the effective ingredient, an formaldehyde-alkanolamine reaction product other than methylolamine. The chemical structure of the formaldehyde-alkanolamine reaction product is not completely known. For example, the following chemical structures are described in Chemical Review, vol. 26 126 (1939) p297-338, United States Patent No. 5,486,605, Japanese Patent Publication No. 46-26903 and Soviet Patent No. 1534029:



wherein R¹ and R³ are substituent groups derived from the amine, and R² is substituent group derived from the aldehyde.--